

**--CROSS REFERENCE TO RELATED APPLICATION**

This application is a continuation of U.S. Patent Application Serial No. 08/497,382  
Pat. No. 6,045,433  
filed June 29, 1995, now ~~allowed~~, which is incorporated by reference herein in its entirety.--;

Page 2, line 2, kindly change "is produced found in" to --is--;

Page 3, line 16, delete "or water.";

Page 6, line 9, kindly change "16" to --18--;

Page 7, line 14, kindly change "wafers" to --wafer--;

Page 7, line 30, kindly change "focusses" to --focuses--;

Page 8, line 2, kindly change "114" to --116--;

Page 8, line 3, kindly change "114" to --116--;

Page 8, line 11, kindly change "focusses" to --focuses--;

Page 8, line 11, kindly change "114" to --116--;

Page 8, line 14, kindly change "114" to --116--;

Page 8, line 17, kindly change "10 - 14" to --10 - 13--.

**IN THE CLAIMS**

Cancel Claims 1-16 and substitute new Claims 1-15 as set forth below.

1. A semiconductor article processing apparatus comprising:  
a processing unit having a working area for processing a top layer of an article;  
an optical measurement station adjacent to said processing unit; and  
a transporter for transporting said article between said processing unit and said  
optical measurement station;  
said optical measurement station located outside said working area and comprising:  
an optical measuring unit for measuring a desired parameter of said top layer  
and;  
a holding unit for receiving and holding said article in a stationary  
measurement position;